



Image

2811

500.39252X00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): K. INOUE et al
Serial No.: 09/698,186
Filed: October 30, 2000
For: A METHOD FOR PRODUCING A SEMICONDUCTOR
DEVICE
Group: 2811
Examiner: D. OWENS
CONF. NO. 3559
Allowed: January 30, 2004

STATEMENT OF SUBSTANCE OF INTERVIEW

MS: ISSUE FEE

Commissioner For Patents
POB 1450
Alexandria, VA 22313-1450

February 13, 2004

Sir:

A personal interview was held with Examiner Douglas Owens (with his Supervisor being present also) on January 15, 2004 as well as a follow-up telephone conference with him on January 23, 2004, the latter led to an agreement for making further amendments via an Examiner's Amendment in connection with rendering the above-identified application allowable. The Examiner and his Supervisor are thanked for their courteousness during those discussions. The following represents a confirmation of the substance of the personal interview as well as regarding the follow-up telephone conference.

I. Regarding the personal interview on January 15, 2004, the Examiner's written summary thereof is provided in form PTOL-413, a copy of which was mailed to applicants on January 23, 2004. In response thereto, the following comments are provided. In the personal interview, the revisions to the claims in the Amendment After Final, also filed on January 15, 2004, were extensively discussed, using as a basis the supportive discussion/rebuttal arguments provided in the Remarks of the Amendment After Final, in connection with obviating the objection of one of the claims and rejection of the claims under 35 USC §112, second paragraph, which were the only issues outstanding at that time involving claims. In that regard, the discussion also included a showing of support in the Specification/Drawings regarding the set forth limitations in the amended claims. In particular, we discussed the masked printing process related to the formation of the stress relaxation layer (the second electrically insulating layer in the claims) and the fact that it is composed of electrically insulating material including particles and, also, showed supportive basis thereof in the Specification/Drawings. With regard to the method of manufacture of the semiconductor device according to the present invention, the relative size of the opening portion of the mask and the fact that overspreading of material occurs upon removal of the mask was also discussed as part of the supportive showing regarding the currently amended claimed subject matter. As part of this supportive discussion, we also referred to the sketches attached to the Amendment After Final.

At the end of the interview, the Examiner did indicate that the revisions made to the claims appear to remove the concerns raised with regard to the objection/rejection under §112, second paragraph. However, the Examiner

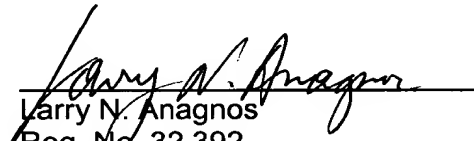
indicated that because he would need to make a more formal review of the amendment filed, he could not, at that time, indicate whether or not the application would be allowed. The Examiner did agree, however, to subsequently call applicants undersigned representative (after the Examiner formally considers the Amendment After Final) for purposes of resolving any additional concerns regarding the claimed subject matter including to suggest additional, minor revisions to render the application allowable. This is basically supported by the Examiner's comments in the interview summary (form PTOL-413).

II. In the follow-up telephone call on January 23, 2004, which was initiated by the above-named Examiner, an agreement was reached to amend dependent claims 52 and 64 via an Examiner's Amendment, thereby rendering the application allowable. The amendments made to those claims are specified under Item 1 in the detailed action accompanying the Notice of Allowability transmittal (form PTOL-37), regarding the above-referenced application. Specifically, the Examiner raised an objection regarding the expression "*the component material ...* " in both of those claims. The undersigned informed the Examiner that the expression was intended to infer the constituent material associated with the claimed second electrically insulating layer. Nonetheless, it was agreed to delete the word "*component*" from that expression since the resulting expression, "*the material ...*," it is submitted, also infers the constituent material of the second electrically insulating layer. The Examiner agreed to enter those further changes by an Examiner's Amendment.

The above is representative of the discussions held during the personal interview as well as during the follow-up telephone conference. Acceptance and formal entry therefor of this statement in connection with completing the record is respectfully requested. [MPEP §713.04]

Please charge any fees due in connection with the filing of this paper to the Deposit Account of Antonelli, Terry, Stout & Kraus, LLP, Dep. Acct. No. 01-2135 (500.39252X00), and please credit any excess fees to such deposit account.

Respectfully submitted,
ANTONELLI, TERRY, STOUT & KRAUS, LLP


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